Network-Based Photomask Data Entry Interface and Instruction Generator for Manufacturing Photomasks

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Serial No. 10/661,187 Filing Date: 09/12/2003
Attorney Docket 068062.0166
REPLACEMENT Sheet 1.of 1

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50 Info Feedback Get a Mask Order Main Menu Account Quote/Account Help Logout Layers Patterns || Placements || || Fractures Business Instructions General Submit In Progress View summary **TestCompany** Please complete the information for each distinct pattern, and press the "Save and Forward" button to progress to Pattern Placement. If the number of patterns or layer information is wrong, please return to the General Info Screen and correct the number of distinct patterns, then return to this screen. -Save And Back Save And Stay Save And Forward -> Patterns 1 - 1 of 1 Layers 1 - 1 of 1 Pattern Pattern Name: Fracture Required? CD Number of Address Digitized **Placements** Units Final, QD Tolerance Layer Digitized? Data Tone Out (μ) $Size(\mu)$ (μ) +/-Pattern application -Save And Back Save And Stay Save And Forward -> \mathcal{P} =Optional for order (V)=Required for this =Required for submit, optional for this screen screen

FIG. 5